

<b>Notice of References Cited</b>		Application/Control No.	Applicant(s)/Patent Under Reexamination	
		09/838,513	CHEN ET AL.	
Examiner		Art Unit		Page 1 of 1
Julio J. Maldonado		2823		

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-5,937,325	08-1999	Ishida, Emi	438/655
	B	US-6,514,859 B1	02-2003	Erhardt et al.	438/664
	C	US-			
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages
	U	Mouroux, Aliette; The Reactive Formation of TiSi <sub>2</sub> in the Presence of Refractory Metals (from V to W), Royal Institute of Technology, Department of Electronics, Stockholm 1,999.
	V	
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a))  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.